

Bi₂Te₂Se – promising material for topological insulators.

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Among Bi₂X₃ family compounds Bi₂Te₂Se crystals are the most promising material for topological insulators. These ternary crystals have a layered structure with the atoms layers sequence of: Te - Bi - Se - Bi - Te. They are characterized by high resistivity at low temperatures around 10K $\rho > 1 \Omega\text{cm}$, [1,2] much higher than crystals of binary compounds as Bi₂Se₃ and Bi₂Te₃ - ($\rho \sim 10^{-3} \Omega\text{cm}$).

Bi₂Te₂Se is obtained by phase transformation in the solid state, which occurs as a result of long time heating the mixture of binary compounds Bi₂Se₃ + Bi₂Te₃ at a specific temperature [3,4,5].

The mixture is formed by Bi₂Te₃ – ‘p – type’ material which properties are determined by high concentration of acceptor defects Bi_{Te} ($p = 2 \times 10^{19} \text{cm}^{-3}$) and Bi₂Se₃ – ‘n- type’ material which properties resulting from the high concentration of donor defects V_{Se} ($n = 2 \times 10^{19} \text{cm}^{-3}$).

The resulting new structure quintuples has the following advantages over the binary compounds Bi₂Te₃ and Bi₂Se₃ [1].

- Generation of V_{Se} defects is suppressed because Se atom trapped between Bi atoms is less exposed to evaporation due to its stronger chemical binding with Bi,
- Formation of the anti-site defects is also suppressed because of the stronger bond between the Se - Bi than Te - Bi,
- Nature of bonds minimizes the additional disorder caused by random impact of Se / Te.

In this work we applied Vertical Bridgman technique (VB) for crystal growth. Crystallization was carried out for the charges compositions of a different ratio of Se / Te : Bi₂ Te_{1.95} Se_{1.05} to Bi₂ Te_{2.2} Se_{0.8}. As the optimum composition Se \approx 1.00 - 1.05 was determined. Specified conditions of heat treatment, resulting in the obtaining of crystals with resistivity $\rho \sim 7.5 \Omega\text{cm}$ at 10 K. After annealing under conditions of 500 °C/520h, we observe transition of conductivity type from n to p. Measurements of resistivity vs T have proved semiconductor behavior from the temperature $T \leq 200$ K. The crystals were characterized by the following methods: Hall measurements in the temperature range 300K – 8K, Scanning Electron Microscopy (SEM), Energy Dispersive X– ray Spectroscopy (EDS), Secondary Ion Mass Spectroscopy (SIMS).X-ray Diffractometry (XRD)

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